

INFORMATION DISCLOSURE CITATION

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ATTY DOCKET NO.
FIS920030330US1

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10 / 673199

Huang et al.

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EXAMINER

Dr. C. Wallace

DATE CONSIDERED

June 10, 2004

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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